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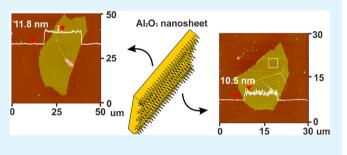
# Free-Floating Synthetic Nanosheets by Atomic Layer Deposition

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#### **Supporting Information**

**ABSTRACT:** Two-dimensional (2D) nanosheets with distinctive properties are often fabricated by exfoliation, hydrothermal synthesis, or vapor-phase reaction. While these approaches are useful to generate nanosheets, we show that free-floating 2D metal oxide flakes with nanometer-scale thickness can also be formed by atomic layer deposition (ALD), where the ALD process allows the thickness and composition to be precisely tuned. In this work, we describe in detail the ALD nanosheet fabrication process and demonstrate how the choice of the sacrificial substrate affects the



subsequent ALD processing and the resulting nanosheet thickness and surface structure. In addition, we introduce the fabrication of organic/inorganic bilayer nanosheets with unique potential applications.

KEYWORDS: nanosheet, atomic layer deposition, sacrificial polymer, organic/inorganic sheet

**R** ecently, many types of two-dimensional (2D) nanosheet materials are being developed and modified for applications in nanoelectronics,<sup>1</sup> biomedicine,<sup>2</sup> energy-storage devices,<sup>3</sup> or biomaterial systems.<sup>4</sup> Since graphene was first isolated from graphite in 2004,<sup>5</sup> a vast amount of research has revealed its unusual electronic and physical properties such as high electron mobility and quantum Hall effect.<sup>6</sup> While graphene has a potential application as a conductor, various oxides<sup>7</sup> including perovskite that have naturally stacked molecular structures also show semiconducting or high  $\kappa$ dielectric properties.<sup>8</sup>

Table 1 summarizes the fabrication methods and thickness range for several nanosheet materials studied to date. The two primary methods for nanosheet fabrication are hydrothermal synthesis and exfoliation from layered compounds.<sup>9–18</sup> Because exfoliation is applied for compounds with naturally stacked molecular structure, it normally produces thinner nanosheets than other methods. Other functional materials, such as silver, gold, or platinum nanoparticles, are often added to nanosheets to enhance the performance in biosensors, batteries, or solar-cell structures.<sup>19-21</sup> Recent work shows that WO<sub>3</sub> formed by atomic layer deposition (ALD) can be converted to WS2 nanosheets by reaction with H<sub>2</sub>S at 1000 °C, and they show good performance in field-effect-transistor structures.<sup>22</sup> The unique functionality of 2D nanosheets is determined to a large extent by the electronic structure associated with full crystallinity, well-defined electronic surface termination and occupation, as well as the planar morphology and high surface area. For example, the electronic structure of 2D graphene rapidly changes with increasing layers, reaching its full threedimensional limit at  $\sim 10$  graphene multilayers,<sup>6</sup> a few nanometers thick. Previously, we showed that ALD can be used to fabricate free-floating metal oxide nanosheets at low

# Table 1. Fabrication Methods and Thicknesses of Nanosheets

methods		materials	thickness (nm)	ref
exfoliation		graphene	<1	9
		$MoS_2$	<1	10
		$MnO_2$	<1	11
		BN	1-7	12
	perovskite	Ca2Nb3O10	~1	13
		K <sub>2</sub> Ln <sub>2</sub> Ti <sub>3</sub> O <sub>10</sub> ,	1-3	14
		KLnNb <sub>2</sub> O <sub>7</sub> ,		
		$RbLnTa_2O_7$		
hydrothermal synthesis		NiO	30-50	15
		ZnO	50	16
		TiO <sub>2</sub>	10-15	17
		BiVO <sub>4</sub>	10-40	18
thermal evaporation		$Ga_2O_3$	20-60	24
		ZnS	tens of nanometers	25
ALD + postdeposition reaction		WS <sub>2</sub>	1-30	22
ALD		$Al_2O_3$ , ZnO, Ti $O_2$	1-17	23

temperatures with thickness in the range of 2D electronic materials.<sup>23</sup> While the ALD materials formed at low temperature do not have full crystalline morphology and well-defined regular surface structure of graphene or other 2D solids, the

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ALD process provides several unique advantages for 2D structure synthesis. Specifically, ALD allows (1) access to a wide material set, beyond known 2D crystal materials, (2) direct scalability to large areas with well-controlled thickness, and (3) facile fabrication of multicomponent heterojunctions and other multiple-compound-layered structures. For example, a TiO<sub>2</sub>/ZnO ALD bilayer nanosheet deposited at 100 and 90 °C has photocatalytic functionality, and the rates of photocatalytic decomposition followed the expected trends in light intensity and thickness. More importantly, bilayer nanosheets composed of TiO<sub>2</sub>/ZnO (2.5 nm/2.5 nm) also deposited at 100 and 90 °C improve the dye degradation rate by ~5 times over TiO<sub>2</sub> nanosheets (2.5 nm). The previous work did not show a detailed analysis of the ALD film nucleation and how it is affected by precursor and substrate choices. This information will be important to further tune and optimize 2D ALD material fabrication.

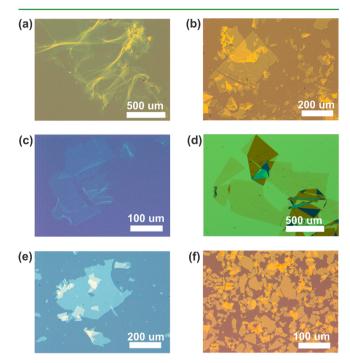
Here, we report in detail the effects of polymers used as a sacrificial layer and ALD materials on nanosheet synthesis. Specific sacrificial polymer substrates include poly(methyl methacrylate) (PMMA), poly(vinyl alcohol) (PVA), and poly(acrylic acid) (PAA). We observed that PVA is most suitable to separate the ALD film with larger size among the tested polymers. From PVA sacrificial layers, the thicknesses of the resulting nanosheets, as observed by ellipsometry and atomic force microscopy (AFM), match precisely the thickness of ALD films formed simultaneously on planar silicon substrates. In addition, we demonstrate the feasibility of using selective polymer dissolution to create free-floating organic/inorganic bilayer sheets, where one nanosheet face is organic and the other inorganic.

Many polymers are known to react with metal–organic precursors during ALD to produce subsurface growth and a graded organic/inorganic interface layer.<sup>26–28</sup> Some polymers, however, including PVA and PAA, have hydroxyl groups present on the surface that can provide good nucleation sites for metal oxide ALD,<sup>27</sup> helping to promote surface nucleation and form an abrupt organic/inorganic interface.<sup>26,28</sup> Carbonyl groups (C==O) in PMMA also react with a precursor to initiate nucleation.<sup>29</sup> In the case of PMMA, however, precursors can diffuse more through the polymer layers than PVA and PAA.

To fabricate nanosheets, sacrificial polymers were spun-cast onto oxidized silicon followed by ALD in a custom hot-wall viscous flow tube reactor. After ALD, the film was cut with a razor blade before polymer dissolution in a liquid solvent. For imaging, nanosheets were collected on clean oxidized silicon and annealed in air to remove residual polymer.

Several experiments tested PMMA as a sacrificial layer for  $Al_2O_3$  nanosheet formation. We found, for example, that when spun-cast PMMA was exposed to 100 cycles of tetramethylammonium (TMA)/water at 90 °C, the subsequent polymer dissolution step in toluene caused the ALD overlayers to rip or tear, especially for the thinner films. However, when PAA was used as a sacrificial layer, its high solubility and low molecular weight (MW) led to very fast dissolution in water.<sup>30</sup> The rapid dissolution likely added stress to the adhered ALD layer, causing the thin layer to break and fracture into small pieces less than 1  $\mu$ m across. The PVA polymer also showed good solubility in water, but it dissolved more slowly, allowing the coated film to flow off more gently, thereby maintaining larger sheets, up to 5 mm across, that were more easily collected and analyzed. If the substrate dissolves too slowly, however, it is difficult to determine the stopping point for complete organic removal. For the PVA materials, we tested materials with high and low MW, 95000 and 16000 g/mol, respectively. The fasterdissolving low-MW PVA tended to show the best dissolution properties, where the speed was high enough to ensure complete organic removal but slow enough to maintain the coating physical structure. Unless otherwise specified, the nanosheet materials described here were fabricated using the low-MW PVA.

Figure 1 shows optical microscopic images of  $Al_2O_3$ ,  $TiO_2$ , and ZnO ALD nanosheets with various film thicknesses. Each



**Figure 1.** Optical microscopic images of  $Al_2O_3$  nanosheets exfoliated from low-MW PVA substrates after (a) 10 and (b) 50 cycles. Also shown are TiO<sub>2</sub> nanosheets formed using (c) 25 and (d) 300 cycles, as well as ZnO nanosheets from (e) 100 and (f) 150 cycles.

type of nanosheet shows properties characteristic of the material. For example, in Figure 1a, the  $Al_2O_3$  nanosheets made using 10 ALD cycles show a folded structure with rounded edges, indicating high flexibility. The wrinkling and overlap evident in the thin ~1.1 nm nanosheets is less evident in the ~5-nm-thick sheets shown in Figure 1b. The thicker films also show a sharper edge shape. Similar to the thin  $Al_2O_3$ , the edges of thin ~1.3 nm TiO<sub>2</sub> nanosheets shown in Figure 1c are curved and rolled up, while the 15.5-nm-thick TiO<sub>2</sub> nanosheets in Figure 1d have angular shape. Also, the thicker ZnO nanosheets tend to break into smaller pieces (Figure 1f), suggesting that thinner sheets are more flexible. The different contrast or color in different regions in Figure 1d is resulted from optical interference due to the stacking or overlap of nanosheets at various points on the surface.

We worked to determine the lower thickness limit for reliable nanosheet fabrication for the materials studied. For  $Al_2O_3$  and  $TiO_2$ , the thinnest sheets we could consistently isolate and optically image were 1.1 and 1.3 nm, as shown in Figure 1a,c. We were also able to isolate  $Al_2O_3$  nanosheets after 5 ALD cycles. These were 0.8 nm thick, as determined by AFM, but we could not obtain a clear optical image. We found it difficult to achieve large-area ZnO nanosheets of less than ~17 nm thick.

Figure 1e shows ZnO nanosheets formed from 100 ALD cycles, corresponding to 17.2 nm. This was close the lower limit of the ZnO layer thickness that we could separate as a stable cohesive nanosheet film. Somewhat thicker ZnO nanosheets are shown in Figure 1f.

When ZnO was deposited on the polymer using less than 100 cycles, dissolving the polymer led to film separation into small flat particles. These particles were small ZnO crystal grains or crystal grain clusters that were not connected into a cohesive film. Figure 2a shows the TEM image of ZnO

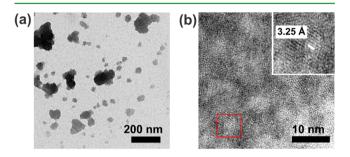


Figure 2. TEM images of ZnO nanosheets from 50 ALD cycles: (a) ZnO nanosheets showing a size of less than 200 nm; (b) lattice spacing of 3.25 Å confirming ZnO crystallinity.

nanosheets from 50 ALD cycles. They mostly show a lateral dimension of less than ~200 nm. Despite of the smaller size, the crystallinity of ZnO is confirmed by TEM images shown in Figure 2b, which shows  $\alpha$  lattice spacing of wurtzite ZnO.<sup>31</sup>

When the nanosheets were formed on the polymer, films were simultaneously deposited onto a clean oxidized silicon wafer, and these monitor wafers were used to measure the film thickness using ellipsometry. The nanosheet thickness was also analyzed by AFM, where the nanosheets were removed from the polymer and transferred to flat silicon wafers as discussed above. Figure 3 shows the layer thickness obtained by ellipsometry and AFM plotted against the number of ALD cycles for  $Al_2O_3$ , ZnO, and TiO<sub>2</sub> nanosheets. In all cases, the nanosheet thickness corresponds well to the thickness of the film directly deposited on silicon, with nanosheet thickness down to the ~1 nm range. This correlation held true even for the small ZnO particles formed with 50 ALD cycles (Figure

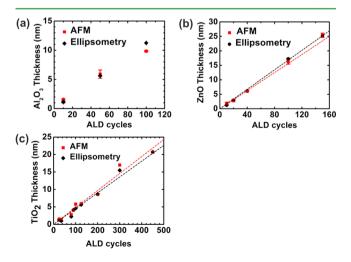
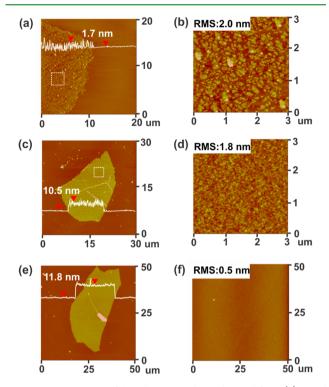


Figure 3. Graphs comparing the nanosheet thickness measured from AFM to the film thickness from ellipsometry depending on the ALD cycles for (a)  $Al_2O_3$  (b) ZnO, and (c) TiO<sub>2</sub>.

3b). These graphs indicate that ALD is an effective way to attain a range of metal oxides in the nanosheet format, where the thickness can be readily tuned by the number of ALD cycles used.

The surface roughness of the resulting nanosheets is also of interest. Figure 4a shows an AFM image of the  $\rm Al_2O_3$ 



**Figure 4.** AFM image of the  $Al_2O_3$  nanosheet obtained from (a) 5 and (c) 100 ALD cycles. (b and d) Magnified images inside the nanosheet marked with the dotted box from parts a and b. (e)  $Al_2O_3$  nanosheet from 100 ALD cycles with a smooth surface. (f) AFM image of spincoated PVA (MW = 16000 g/mol) used as a sacrificial layer.

nanosheet obtained after 5 ALD cycles. Figure 4b displays a more magnified image collected from the 3  $\mu$ m box region in Figure 4a, showing a root-mean-square (rms) roughness of  $\sim$ 2.0 nm. This thin nanosheet is a single continuous 2D film with rough surface texture, and the contrast in the AFM image makes it appear as a composite of many individual flakes. During the Al<sub>2</sub>O<sub>3</sub> nucleation phase, i.e., the first 10-20 ALD cycles, small  $Al_2O_3$  clusters coalesce to form a continuous film,<sup>26,28</sup> so the surface roughness in the ~5 nm nanosheets likely relates to film nucleation on the polymer substrate. Parts c and d of Figure 4 show similar AFM images at the same scale obtained from a 10.5-nm-thick Al<sub>2</sub>O<sub>3</sub> nanosheet formed using 100 ALD cycles. This layer shows an rms of 1.8 nm, nearly the same as the 5-cycle sample. However, Figure 4e shows a different nanosheet formed in the same run as the one in Figure 4c,d. This second nanosheet shows a remarkably smoother surface, with a rms roughness of  $\sim 1.1$  nm. This difference in the nanosheet roughness is attributed to different roughness on the "front" and "back" of the nanosheets. Surveying a random set of the thicker nanosheets collected from a single batch shows a roughly binary distribution of surface roughness, with half showing relatively rough surface texture and half showing smoother texture. We ascribe the rougher texture to the "bottom" of the nanosheet, which is the side originally in contact with the polymer substrate, and the smoother texture to

the "top" of the nanosheet on the deposited film face. To help confirm this assignment, Figure 4f shows an AFM image of the sacrificial PVA layer after spin coating before the ALD nanosheet coating step. The PVA layer shows an rms roughness of 0.5 nm. Even though PVA has surface hydroxyl groups that can readily react with TMA, some subsurface diffusion may occur, leading to roughness on the "bottom" of the nanosheet that exceeds the roughness from bottom to top in the thicker nanosheets suggests that the roughness evolves from surface processes during film growth rather than conformal transfer of substrate texture to the deposited coating. Variation in the nanosheet thickness after 100 ALD cycles in Figure 4c,e is attributed to differences in the residual polymer remaining after annealing at 450-500 °C for 1 h.

We note that some of the nanosheets retain large lateral size (Figure 1a-e), while the thicker ZnO layers tend to break upon polymer dissolution (Figures 1f and 2). The more amorphous Al<sub>2</sub>O<sub>3</sub> and TiO<sub>2</sub> nanosheets appear to be more flexible, allowing larger sizes to be attained.

We also explored the creation of organic/inorganic bilayer heterojunction sheets. These layers were also formed on a thin (<1000 nm) sacrificial PAA or PVA layer formed from an aqueous solution. A second polymer, in this case PMMA dissolved in tetrahydrofuran, was spun coat onto PAA or PVA. Because PMMA dissolves in different solvents from PAA or PVA, they are expected to be immiscible. The resulting polymer stack is then exposed to 100 ALD cycles of TiO<sub>2</sub> at 100 °C or 100 ALD cycles of ZnO at 90 °C. Dissolving PAA or PVA then results in a free-floating organic/inorganic bilayer sheet stack or junction. Parts a and b of Figure 5 show digital photographs of

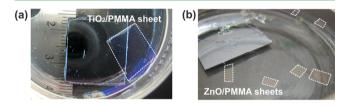


Figure 5. Pictures of (a)  $TiO_2/PMMA$  bilayer sheets separated during PAA dissolution and (b) ZnO/PMMA bilayer sheets during PVA dissolution.

 $TiO_2/PMMA$  and ZnO/PMMA bilayer sheets separated from the substrate after dissolution of PAA or PVA. For the  $TiO_2/$ PMMA bilayer sheet, the substrate was scribed once using a razor blade before PAA dissolution, resulting in large nanosheets, ~1 cm across (Figure 5a). For the ZnO/PMMA bilayer sheets, several razor scribes were cut into the coated sample, resulting in a larger number of smaller nanosheets, a few millimeters across (Figure 5b).

Several researchers study inorganic materials coordinated with organics for a variety of applications. For example, Stroock et al.<sup>32</sup> demonstrated free-floating polymer flakes with well-defined size and shape using microcontact printing and selective surface polymerization. Also, Vendamme et al.<sup>33</sup> showed free-standing ~35-nm-thick organic/inorganic interpenetrating network membranes formed by liquid-phase sol–gel methods. The ALD organic/inorganic bilayers are unique in that they have separate organic and inorganic regions, opposite-facing on different sides of the heterogeneous nanosheet. Such hybrid materials may find unique uses in the fields of electronics, optics, or bioengineering.<sup>34</sup>

This work demonstrates ALD as a viable means to prepare free-floating nanosheet materials. The results describe the role of the sacrificial polymers and ALD process on the resulting structures. We find that PVA with MW = 16000 g/mol performed well as a sacrificial substrate, allowing the formation of synthetic Al<sub>2</sub>O<sub>3</sub>, ZnO, and TiO<sub>2</sub> nanosheets with thickness down to 1 nm and a lateral size-to-thickness ratio exceeding 20000. The nanosheet thickness measured by AFM correlates directly with the thickness of films formed simultaneously on planar solid surfaces. The surface roughness of the resulting nanosheets reflects processes that occur during film nucleation and growth rather than transferring the substrate roughness through conformal film evolution. For some processes, a binary distribution of surface roughness values is obtained, likely because of different roughness on the "front" and "back" of the nanosheets. ZnO nanosheets consisting of dispersed crystal grains or clusters with smaller lateral dimension were obtained using 50 ZnO ALD cycles on PVA. Moreover, the ALD process allows the facile fabrication of multilayered nanosheet structures, including inorganic/inorganic and organic/inorganic bilavers.

#### ASSOCIATED CONTENT

#### **S** Supporting Information

Experimental details. This material is available free of charge via the Internet at http://pubs.acs.org.

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#### Notes

The authors declare no competing financial interest.

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